



Heterogeneous Systems-on-Wafers

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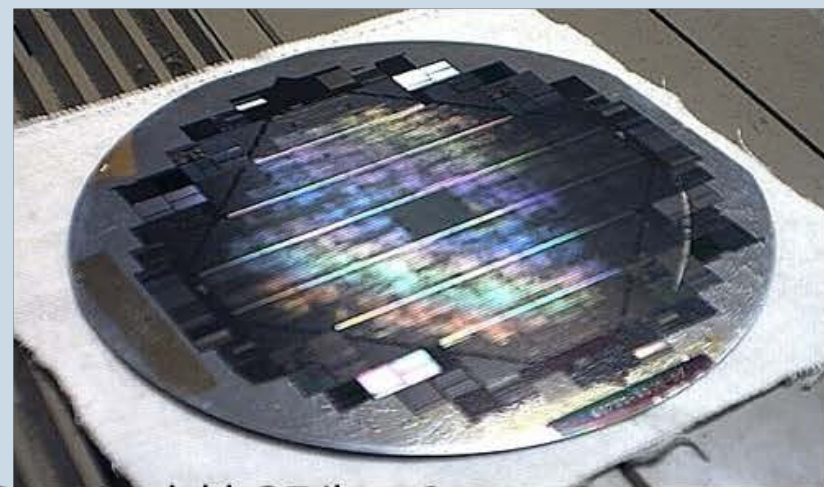


3D Heterogeneous Integration: Common Heterogeneous Integration and IP Reuse Strategies (CHIPS)



*"It may prove to be more economical to build large systems out of smaller functions, which are **not packaged separately**—packaged—and **but intimately interconnected.**"*

—With apologies to Gordon Moore



Gene Amdahl @Trilogy Systems

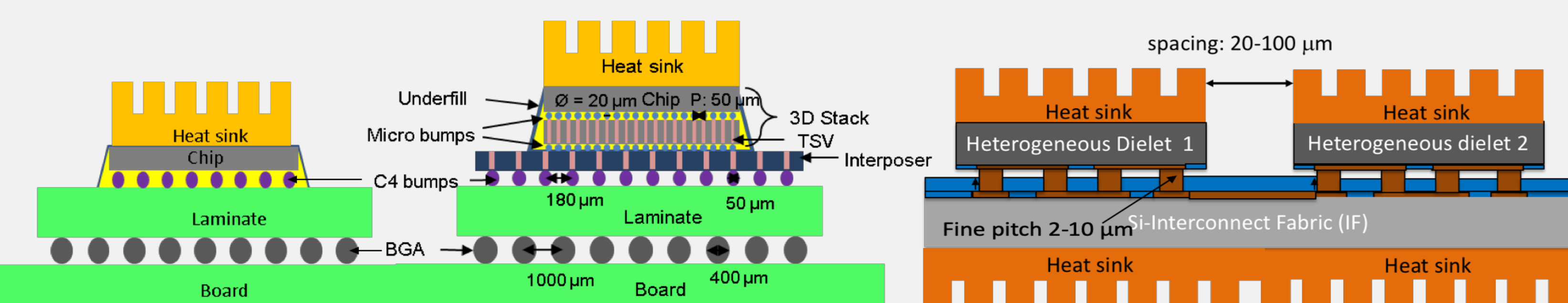
Early attempts at monolithic Wafer-Scale-Integration failed mainly due to yield limitations
Let's revisit this problem using advanced packaging and build Heterogeneous Wafer Scale Systems

Our approach:

- Replace PCB with a silicon wafer with fine pitch wiring - the Silicon Interconnect Fabric (Si IF)
- Assemble heterogeneous dielets on the Si IF at 2-10 μm dielet-to-Wafer pitches (vs $\sim 500 \mu\text{m}$)
- Place these dielets as close as possible to each other i.e. 20-100 μm spacings (vs $\sim \text{mm}$)

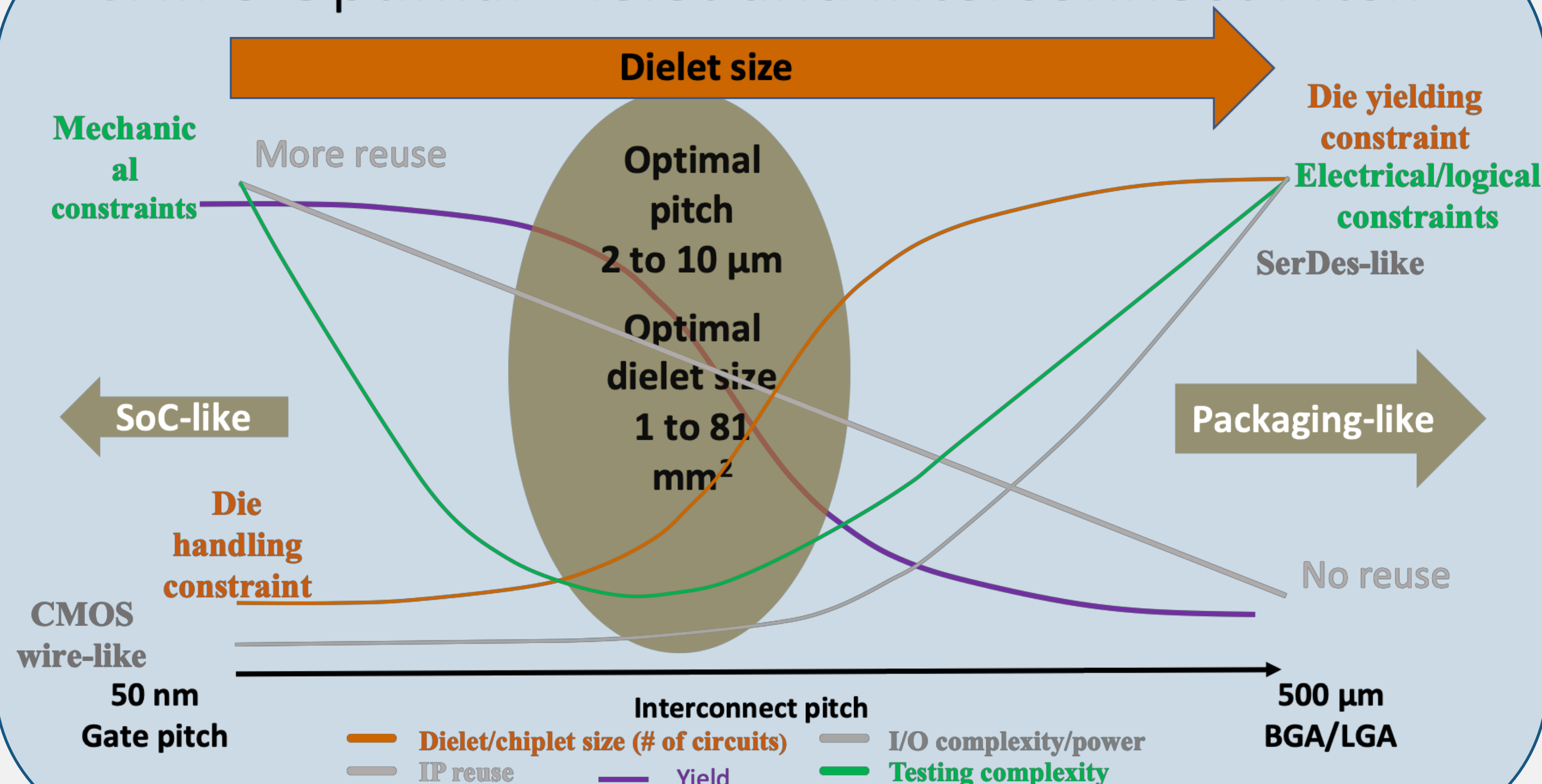
You now have a Heterogeneous System-on-Wafer

PCBs vs. 3D/Interposer vs. Si-IF



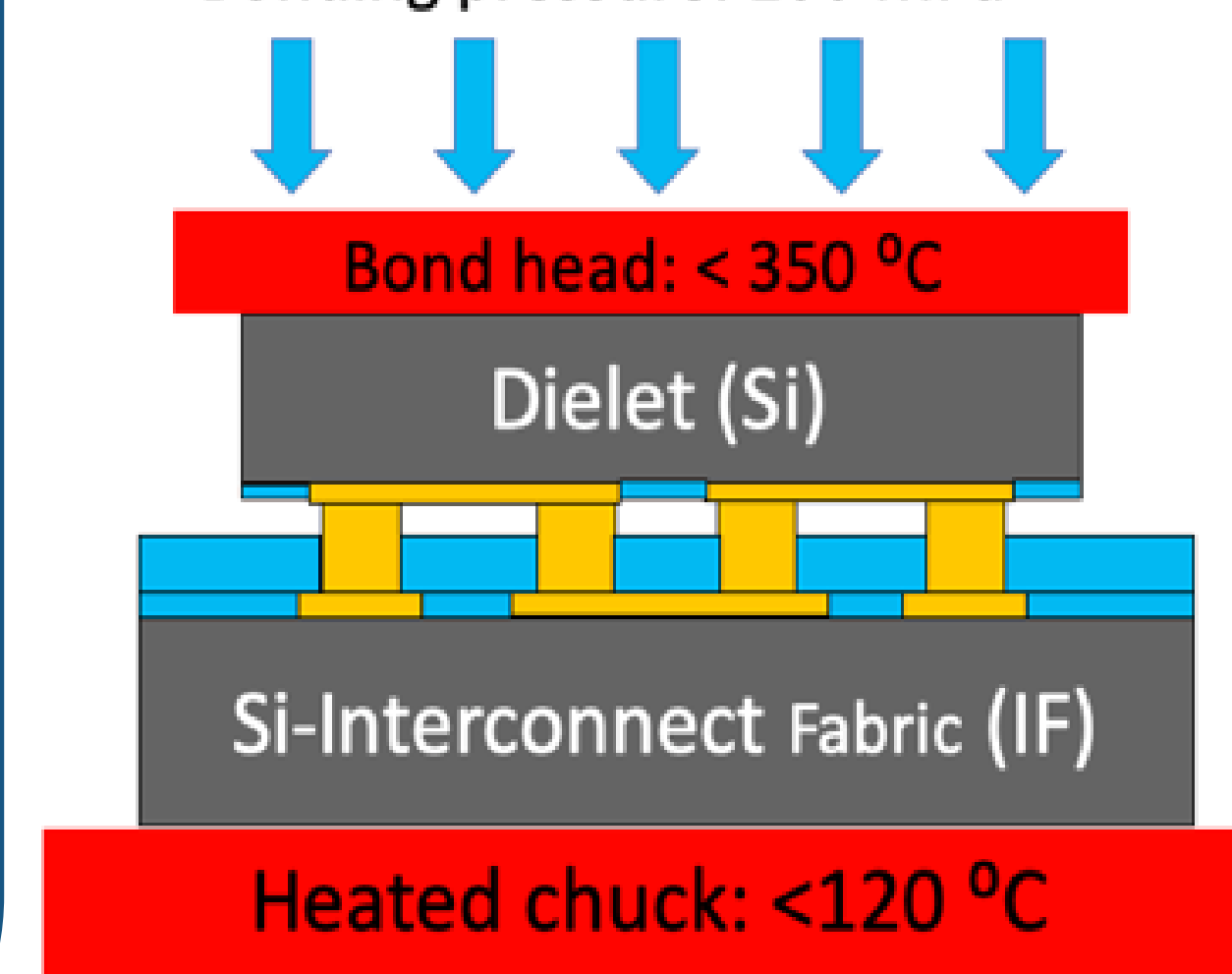
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|---|--|--|
| <ul style="list-style-type: none"> • Multiple packaging levels • Limited heat sinking • Solder based interconnects • Underfill needed • Limited by BGA pitch | <ul style="list-style-type: none"> • PCB with and extra level • Size limitation • Needs expensive TSVs • Interconnect pitch: 50 μm • Thermal issues | <ul style="list-style-type: none"> • Single package level • Excellent heat sinking • Metal-metal interconnects • No underfill • Complete system integration |
|---|--|--|

CHIPS Optimal Dielet and Interconnect Pitch



Thermal Compression Bonding: Cu terminated dielets to Cu pillars on Si-IF

Bonding pressure: 100 MPa



Challenges:

- Surface roughness
- Surface cleanliness

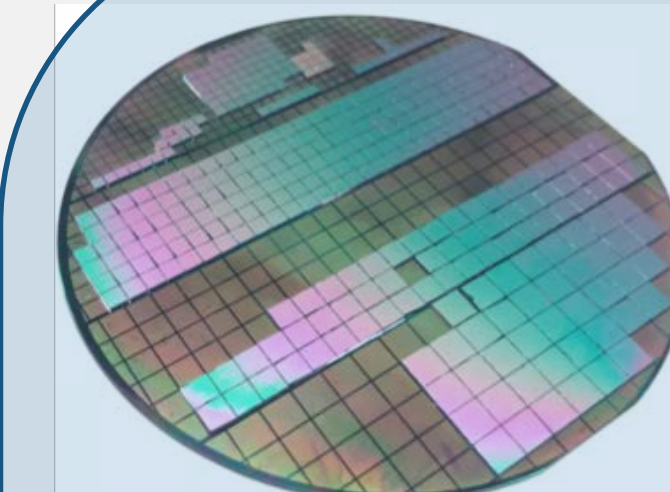
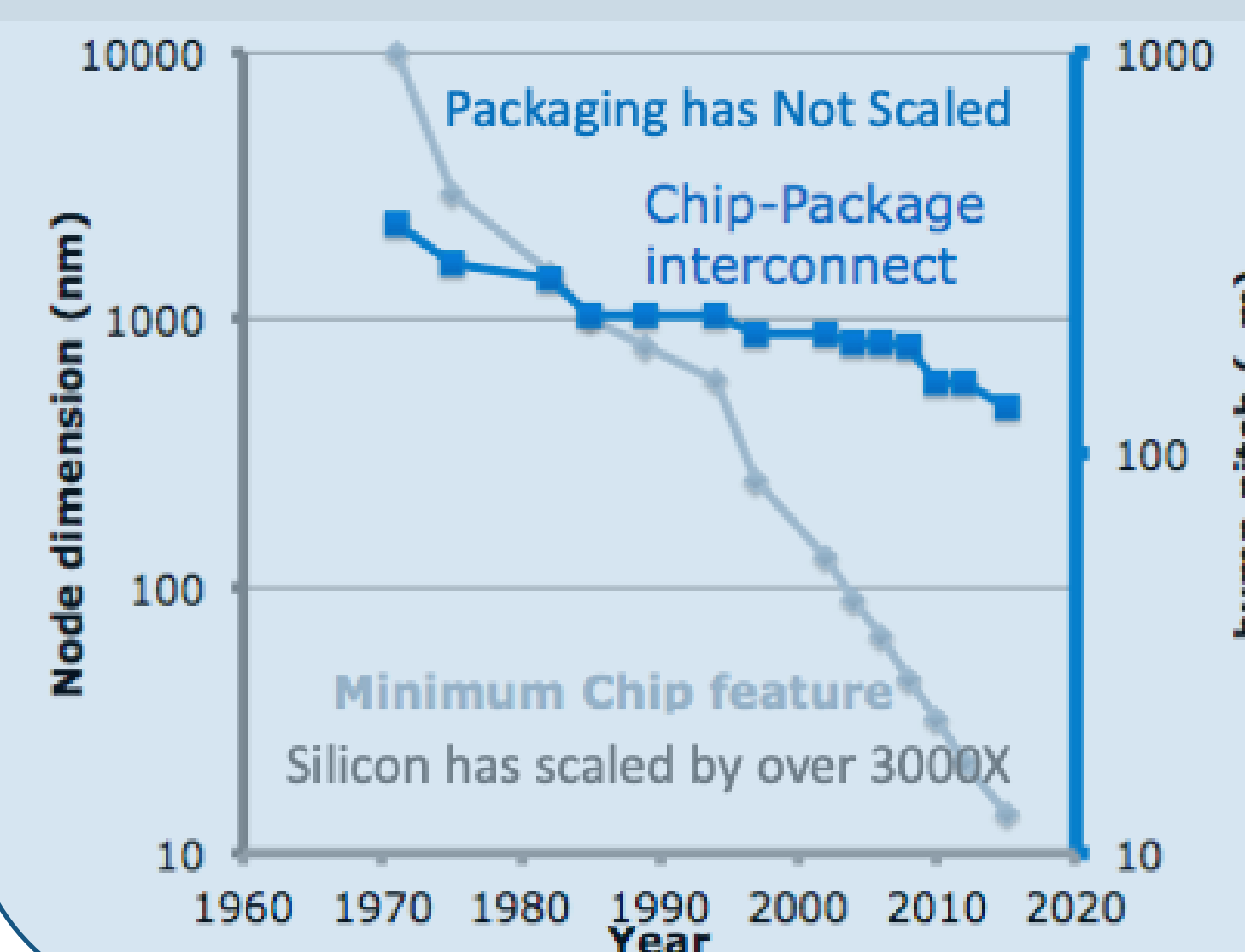
Process Parameters

- In situ cleaning
- Pressure
- Temperature
- Time

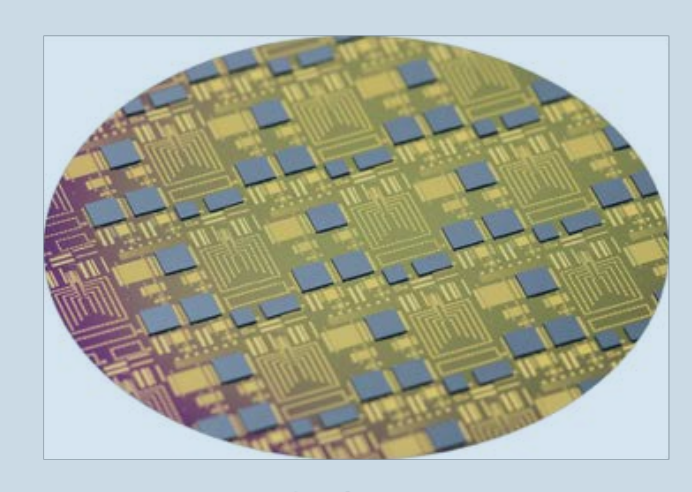
Material Parameters:

- Diffusivity
- Plastic Deformation

Need a Moore's Law for Packaging!



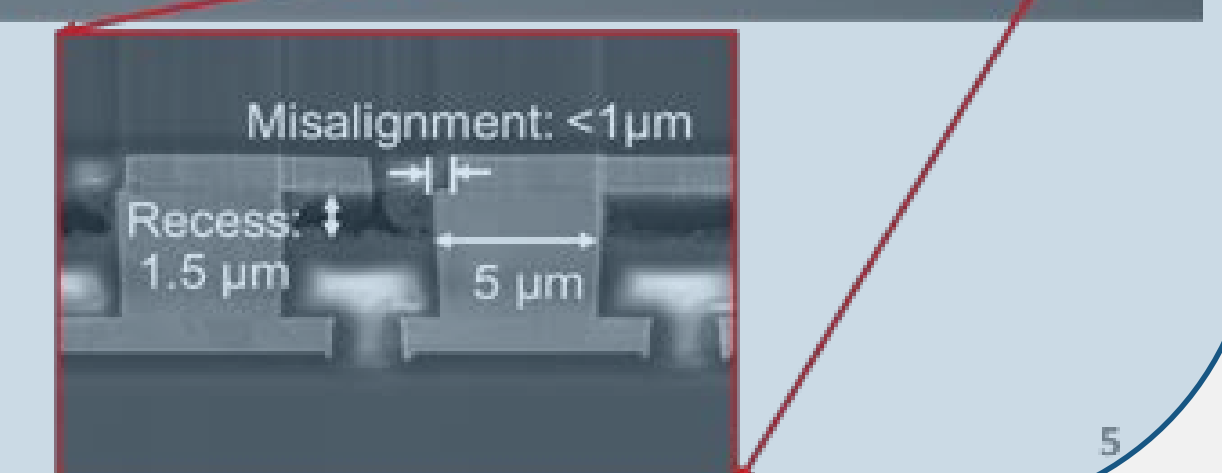
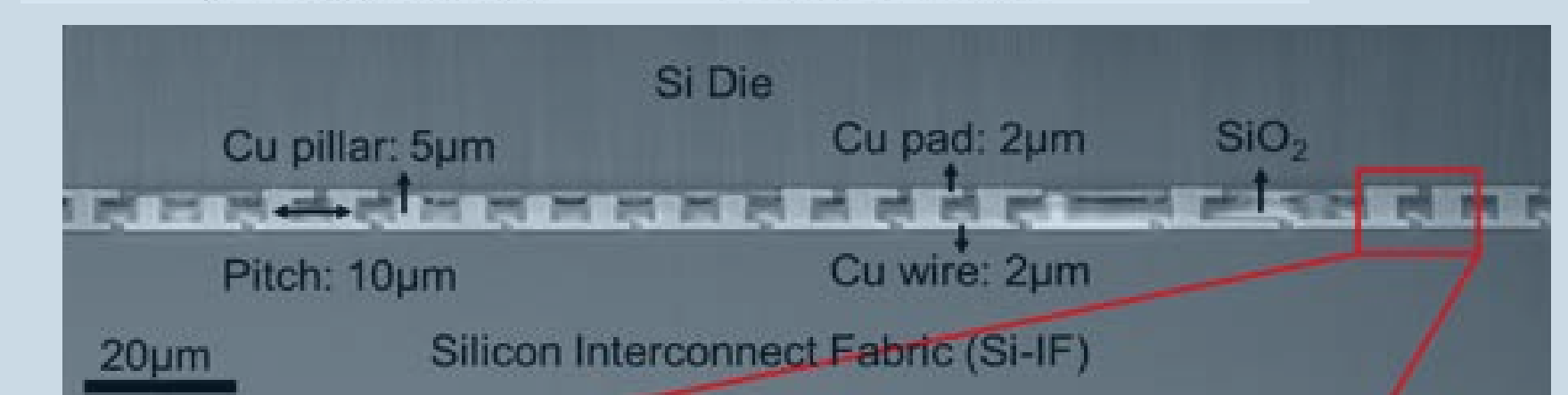
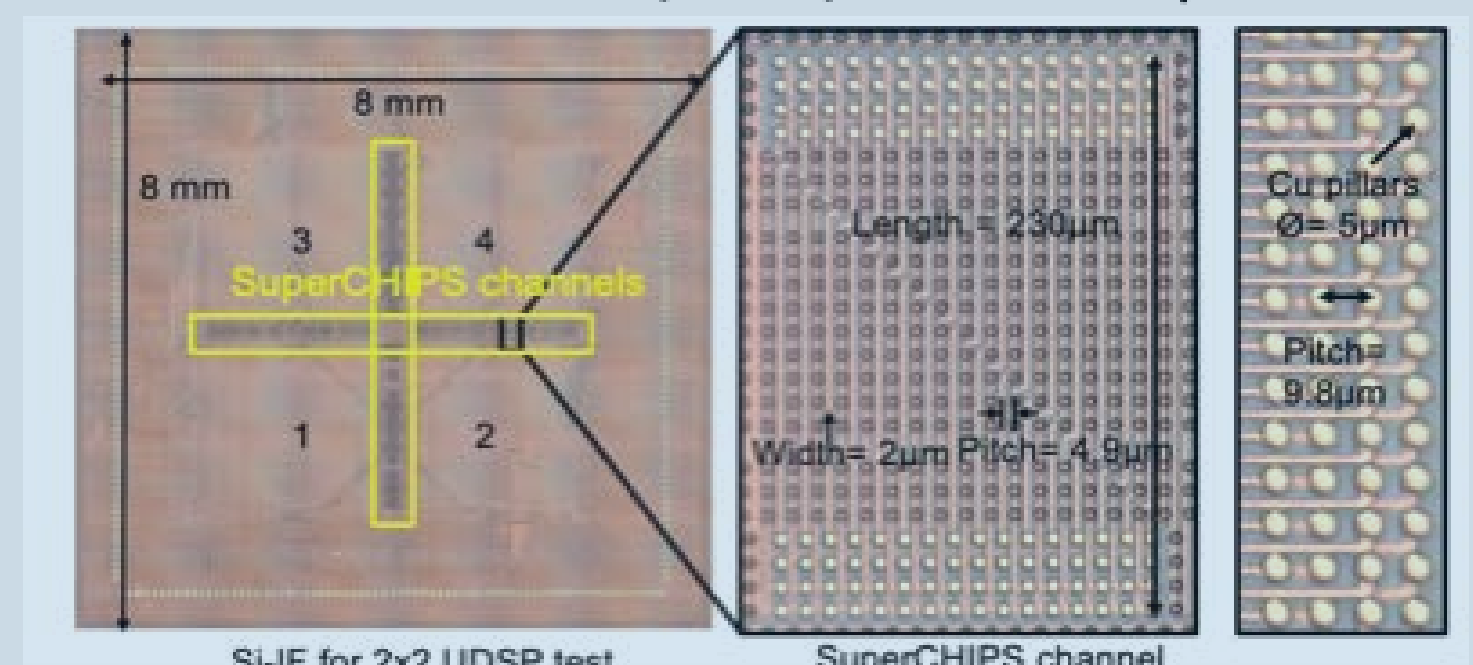
Si dielets on Si IF



InP dielets on Si IF

- Up to 4 Si IF wiring levels
- Pillar pitch 10 μm - legacy compatible ($> 200\mu\text{m}$)
- $\pm 1 \mu\text{m}$ alignment
- Cu (Si dielets) or Au (III-V dielets) terminations - No Solder
- Both shear force and resistance better than BGAs

2 wiring levels & 4 rows of pillars
=>Effective pillar pitch is $< 2.5\mu\text{m}$



Small dielet integration on Si-IF enables:

- SoC performance (latency, bandwidth)
- $> 100\text{x}$ reduction in energy per bit
- Significantly reduced time to market
- 10-50X reduction in NRE
- IP reuse
- Heterogeneity

Interconnect pitch/protocol	10 μm on Si-IF <i>SuperCHIPS</i>		50 μm on Interposer <i>HBM2</i>	400 μm on PCB/ <i>SerDes</i>	Improvement
	Async	Sync			
No of links/mm	200		20	2.5	10-100X
Latency (ps)	35	1 clock cycle	240 ^[2]	$\sim 1,000$	7-30X
Data-rate/link (Gbps)	10	4	2 ^[3]	64 ^[1]	0.1-5X
Energy/bit (pJ/b)	< 0.04	< 0.2	3.8 ^[2]	5.1 ^[1]	20-120X
Bandwidth/mm (Gbps/mm)	8000*	1600*	170 ^[3]	90	10-100X

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